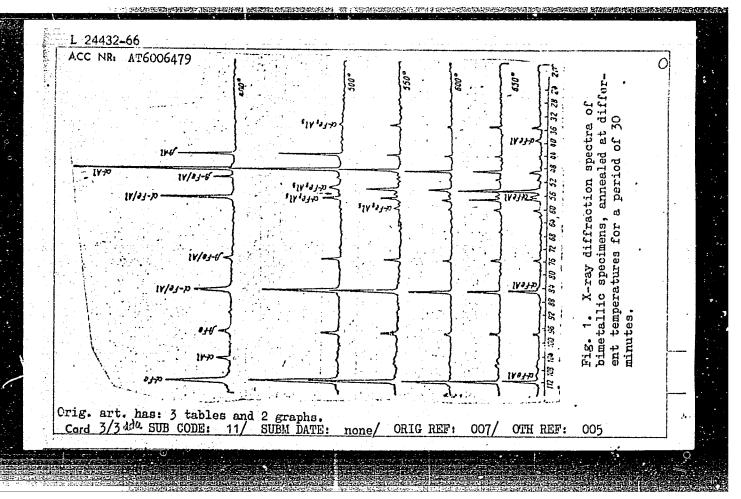
ACC NR: AT	006477				-	0
This explanation 1962, t. 10)	tion was prop . Orig. art.	osed by V. I. has: 6 graphs	Arkharov and	Ye. B. Blank	ova (FMI, vyp	. 1,
SUB CODE: 1	1/ SUBM DATE	: none/ ORIC	REF: 004/	OTH REF: 00	<b>1</b>	
						•
						:
					•	
Card 2/2 dda						
Card 2/2 Ma				·		

	L 24432-66 FWT (m)/T/FWP(+) IJP(c) JD/JH ACC NR. AT6006479		
37	SOURCE CODE: UR/2680/65/000/024/0124/012	<u>7</u> 1	
	31	2 1	
- 2			
	ORG: State Scientific Research and Design Institute of Alloys and Nonferrous  Metalworking, Moscow (Gosudarstvennyy nauchne issledowntall by		
	Metalworking, Moscow (Gosudarstvennyy nauchno-issledovatel skiy i proyektnyy institut splavov i obrabotki tsvetnykh metallov)	1	
	TITLE: The reaction diffusion of iron into aluminum		
	SOURCE: Moscow County, 18 27		
	SOURCE: Moscow. Gosudarstvennyy nauchno-issledovatel'skiy i proyektnyy institut obrabotka tsvetnykh metallov. Trudy, no. 24, 1965. Metallovedeniye i	1.	
	Obracotka tsvetnykh metallog i and   Obracotka tsvetnykh metallovedenive i	- -	
	metals and alloys), 124-130 (Metal science and the treatment of nonferrous		3.5
	TOPIC TAGS: aluminum, iron, aluminum compound, intermetallic compound/ AVOOO		
	aluminum, Armeo Airon aluminum compound, intermetallic compound/ AV000		
	ABSTRACI: This investigation was and and		
	ABSTRACI: This investigation was undertaken to resolve the present controversy concerning the nature of the compounds formed in the solid state diffusion of iron significant.		
	The aliminum. Flootness and a second of the sould be take diffusion of the		
	The coating of the anaders		
	OugldChillstic bliminum		
	Shaskol'skaya (ZhTF, 1964, vyp. 11, t. 14, str. 12831290). The experimental results		
L			
DATE		Z.,	
- 			
		O	

ACC NR. AT6006	The second			:		0
are presented in diffusion of iro compound FeAlz.	n graphs and table on into aluminum b At higher temper	s (see Fig. 1 egins at 3500 atures (up to	). It was for and gives rived 400C) Fe_Al.	ound that ise to the is forme	the solid formation d, and at (	state of the 6500 the
formation of Fe	Al takes place.		2	)	. •	
					•	
				• • • • • • • • • • • • • • • • • • •		
				."		
					· ·	
				•		
		ental Artika				
Card 2/3.						

"APPROVED FOR RELEASE: 03/13/2001 CIA-RDP86-00513R000928910004-8

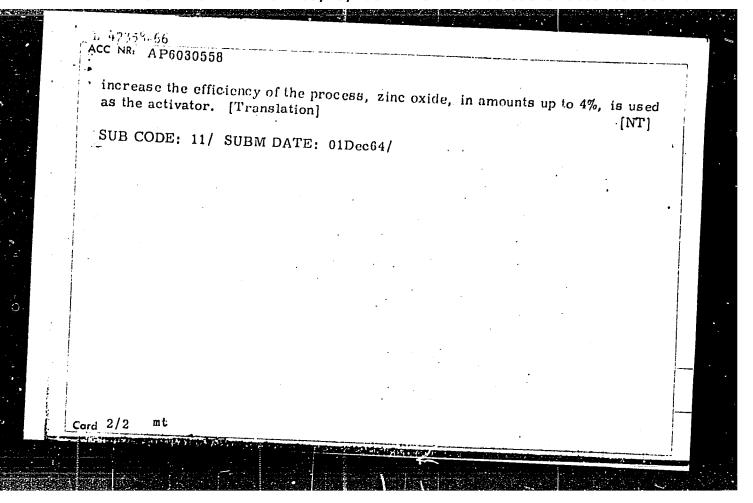


L 28857-66 ACC NR: AP6010411 SOURCE CODE: UR/0126/66/021/003/0466/0467 Layner, D. I.; Bay, A. S.; Gil'dengorn, I. S. Giprotsvetmetobrabotka TITLE: On the mechanism of the oxidation of iron SOURCE: Fizika metallov i metallovedeniye, v. 21, no. 3, 1966, 466-467 TOPIC TAGS: metal oxidation, iron, iron compound, physical diffusion, ion, physical ABSTRACT: There is a discrepancy between two theories of this mechanism. Thus, Pfeil (Iron and Steel Inst., 1929, 119, 501) established that the dominant factor in the oxidation of iron is the diffusion of Fe ions through the scale, whereas Davies et al. (J. Metals, 1951, 3, 10, 889) and Himmel et al. (J. Metals, 1953, 5, 6, 827) believe that oxygen diffusion accounts two-thirds for the formation of Fe<sub>3</sub>0<sub>4</sub> layers and entirely for the formation of Fe<sub>2</sub>O<sub>3</sub> layer and consider the diffusion of cations as the dominant factor in the oxidation of iron. To clear up this discrepancy, the authors performed a simple experiment: specimens of armco iron were oxidized in air at 1000°C until a Fe<sub>2</sub>O<sub>3</sub> layer several microns thick had formed. After this, a platinum tag (wire of 100-µ diameter) was placed on the surface of the specimen without removing it from the furnace and the oxidation was continued for several hours. 1/2 Card UDC: 669.018.85: 620.193

	10411				0
Subsequent i	nvestigation sho	wed that the tag	lay deep in th	ne layer of w	stite. Addi-
the iron sho	wed that the pen	etration of the same s	separated (toge	ther with the	tag) from
with creep.	rnese rindings c	ontradict the the	orv of Davies	et al and ut	mmal at al
Arkharov (Ok	islenive metallo	v the mechanism su v. Sverdlovsk. Me	iggested by Ffe	il as well as	by V. I.
LUGG GL HIZH	Lemberatures in	IR KR_II. IAVAY io.	the fines to a		1 4
scale forms	at the Fenon-On	ng to the reducti interface.) Orig	on of the Fe <sub>2</sub> 0	oxide by Pe	ions. The
			Note that the second of the se		
SUB CODE:	11,07/ SUBM	DATE: , 09Jun65/	ORIG REF: 00	1/ OTH REF:	003
1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1					
,					

## CIA-RDP86-00513R00092891000 "APPROVED FOR RELEASE: 03/13/2001

	"APPROVED FOR RELEASE: 03/13/2001 CIA-RDP86-00513R000928910004-8
	The importance of an activator. To raise the yield of diphenyldichlorosilane and to the presence of an activator. To raise the yield of diphenyldichlorosilane and to the presence of an activator. To raise the yield of diphenyldichlorosilane and to the presence of an activator. To raise the yield of diphenyldichlorosilane and to the presence of an activator. To raise the yield of diphenyldichlorosilane and to the presence of an activator. To raise the yield of diphenyldichlorosilane and pinchological phenyldichlorosilane and to the presence of an activator. To raise the yield of diphenyldichlorosilane and to the presence of an activator. To raise the yield of diphenyldichlorosilane and to the presence of an activator.
, c	silanes of an activator.
	050
•	Card 1/2



ACC NR: AP7005141

SOURCE CODE: UR/0126/66/022/004/0640/0640

AUTHOR: Pakhomov, V. Ya.; Kunakov, Ya. N.; Kachur, Ye. V.; Layner, D. I.

ORG: Scientific Research and Design and Planning Institute of the Rare Metals Industry (Nauchno-issled. i proektnyy institut redkometallicheskoy promyshlennosti)

TITLE: The effect of microinhomogeneity on the critical points of superconducting alloys

SOURCE: Fizika metallov i metallovedeniye, v. 22, no. 4, 1966, 640

TOPIC TAGS: critical point, superconducting alloy, lattice defect, grain structure, homogenization heat treatment, cast alloy

ABSTRACT: The effect of a homogenization anneal on the critical current density of Nb-46% Ti and alloy-2 was studied. The purpose of this heat treatment was to eliminate intercrystalline liquation which exists in the as-cast alloys. It is known that the Lorentz force can cause a creep of magnetic current that may result in the loss of superconductivity. Different types of metallic defects (inhomogeneities, dislocations, internal stresses, etc.) may act as stabilizers against the creep. For the experiments, 40-gram ingots were melted in a radiant arc furnace with tungsten electrodes in a purified helium atmosphere and homogenized in a vacuum furnace at 1500°C. The homogenized ingots were cold reduced into 0.25 mm diameter samples. All samples

Card 1/2

UDC: 537.312.62

### ACC NR: AP7005141

had similar cold reductions. Critical current densities were measured in a transverse magnetic field of 16 kilocersted at 4.2°K. The critical current density was given as a function of ingot homogenization time which ranged from 1 to 5 hours. In both alloys, the critical current density was lowered by homogenization. The critical current density for Nb-46% Ti úccreased linearly from about 1.8°10° a/cm² in the as-cast condition to about 10° a/cm² after 5 hours of ingot homogenization. Alloy-2 dropped sharply from 2°10° a/cm² to about 10° a/cm² after 1 hour of ingot homogenization, and remained constant thereafter. All of the samples had a similar dislocation density of 10¹¹²-10¹² cm², characteristic of severely deformed metals. The microstructure of as-cast ingots showed intercrystalline liquation, which decreased as a function of homogenization time. After 5 hours at 1500°C, almost all of the liquation was absent in both alloys. Analogous results were obtained in the alloys Nb-75% Zr and 65 BNT in which the critical current density after homogenization changed from 1.3°10° and 2°10° to 7.8°10³ and 1.2°10³, respectively. Orig. art. has: 1 figure.

SUB CODE: 20,11/ SUBM DATE: 02Feb66/ OTH REF: 001

Card 2/2

ACC NR: AP6036114

(N)

SOURCE CODE: UR/0365/66/002/006/0692/0699

AUTHOR: Layner, L. I.; Slesareva, Ye. N.; Tsypin, M. I.; Bay, A. S.

ORG: Scientific Research Institute for Alloys and the Working of Nonferrous Metals (Nauchno-issledovatelskiy institut splayov i obrabotki tsvetnykh metallov)

TITIE: Oxidation mechanism of titanium alloys containing up to 11% aluminum

SOURCE: Zashchita metallov, v. 2, no. 6, 1966, 692-699

TOPIC TAGS: titanium containing alloy, metal oxidation, aluminum

ABSTRACT: A study was made of binary titanium-aluminum alloys containing 0.01, 0.87, 2.85, 5.05, and 11.20 weight percent aluminum. The alloys were twice melted in an arc furnace with consumable electrodes, and then forged, rolled, annealed, and planed to eliminate the oxygen-saturated layer. The polished samples had dimensions of 1.2 x 1.2 x 1.5 cm, with an opening 2 mm in diameter. A day before the experiment, the samples were degreased in benzene and stored in a desiccator. The samples were charged into a resistance furnace with a working chamber 150 x 400 mm, heated to the given temperature. Temperature variations in the furnace did not exceed ± 5%. In some of the experiments steam was supplied at a temperature of 600°. In this case, the atmosphere of the furnace contained 60-70% water vapor. The rate of oxidation was determined by the gravimetric method. The effect of alloying on heat resistance was evaluated from the

Card 1/2

VDC: 620.193.5

ACC NR: AP6036114

relative change in weight of the samples. Phase analysis of the scale and of the layers beneath the scale was done on a Type URS-501 diffractometer. The experimental results with respect to the relative weight change of the alloys as a function of temperature, holding time, and composition of the gas medium are shown in a series of curves and tables. Based on the experimental data it is concluded that two basic mechanisms play a role in the process of the oxidation of titanium-aluminum alloys: 1) acceleration of diffusion through the scale due to a shift of the ionic equilibrium as a result of the entrance of trivalent aluminum ions into the titanium dioxide as a result of the entrance of trivalent aluminum ions into the titanium oxide in the lattice; 2) slowing down of the oxidation when the amount of aluminum oxide in the scale increases to such an extent that there is formed a more or less thick layer of Al<sub>2</sub>O<sub>3</sub> which hinders the diffusion of the titanium ions. Orig. art. has: 2 figures and 4 tables.

SUE CODE: 11/ SUBM DATE: 21Dec65/ ORIG REF: 015/ OTH REF: 012

Card 2/2

9.4300 (1035,1138,1143)

\$/070/60/005/005/015/017 E132/E360

AUTHORS:

Mil'vidskiy, M.G., Layner, L.V. and

Ovsyannikova, S.P.

TITLE:

Dendritic Structure in Single Crystals of Silicon

Grown from the Melt by Czochralski's Method

PERIODICAL: Kristallografiya, 1960, Vol. 5, No. 5, pp. 817 - 818

TEXT: A dendritic structure was found in a number of specimens of single crystals of silicon, Poriented to show the 111 plane and etched in a mixture of HF, HNO<sub>5</sub> and (CH<sub>2</sub>CO)<sub>2</sub>O in the ratio

of 1:3:5. The origin of this structure appears to be crystallisation at a temperature below the temperature at which certain impurities separate out from the melt. Here, dendritic growth is most frequent when crystals are pulled out of technical silicon (purity 99.7 - 99.8%). Dendrites are developed in the 111 planes and when a section across them is cut in the 111 plane a picture is obtained which is very like that found in the octahedral slipping in crystal of Ge and Si when dislocations are developed. In purer materials dendrite formation is connected Card 1/2

S/070/60/005/005/015/017 E132/E360

Dendritic Structure in Single Crystals of Silicon Grown from the Melt by Czochralski's Method

with the presence of impurities (Ta, Ti, Fe, Mo) with solubilities within the limits  $10^{-3}$  to  $10^{-4}\%$ . Ingots grown from supercooled melts also show this dendritic structure. It is most readily shown on surfaces which have suffered light oxidation as a result of etching. The growth of dendrites on slow cooling of a melt in a vacuum has been observed (on the free surface of the melt). The purer the Si the greater the supercooling at which dendritic growth begins and the slower the growth is. There are 5 figures and 5 references: 2 Soviet and 1 English.

ASSOCIATION:

Gosudarstvennyy nauchno-issledovatel¹skiy i proyektnyy institut redkometallicheskoy

promyshlennosti (State Scientific Research and Design Institute for the Rare Metal Industry)

SUBMITTED:

April 4, 1960

Card 2/2

S/181/61/003/001/039/042 B102/B204

24,7500 (1136,1143,1160) AUTHORS: Mil'vidakiv.

Mil'vidskiy, M. G. and Layner, L. V.

TITLE:

Twins and dislocations in silicon single crystals

PERIODICAL: Fizika tverdogo tela, v. 3, no. 1, 1961, 289-296

TEXT: It was the aim of the authors to study the twin formation in the growth of silicon single crystals, and to investigate the interaction between twins and dislocations. Twins containing Si single crystals, grown in the [111] and [110] directions by the Chokhral Dkiy method were used for the purpose; the position of the twins was determined after etching in 10% NaOH at 65-80°C (20 min); the dislocation density was determined from the etch pits in longitudinal and cross sections of crystals with (111) orientation. For counting the etch pits an MMM-8M (MIM-8M) microscope was used (225x). The orientation of the specimens was determined from Laue patterns. The outward appearance of the twins is shown in Fig. 1 (a - growth axis [111]; b - [110]). The experimental results indicate that the twin boundary actually hinders dislocations

Card 1/6

CIA-RDP86-00513R000928910004-8

89298 S/181/61/003/001/039/042 B102/B204

Twins and dislocations in silicon...

"但是在大學的學術,但是是在學術學的學術學的學術學的學術學的學術學的學術學

from penetrating into the twinned part of the crystal; this is explained by the fact that on the twin boundary, dislocations accumulate (Fig. 4) and form a glide plane. However, it also happens that dislocations slip through this barrier (Fig. 3) as, e.g., in the case of crystals growing in the [110] direction. If one assumes that an axial temperature gradient during the growth of the crystal block is the main reason of sliding, it is possible to estimate the probability of sliding in the crystal or in the twin. In this case, the entire tangential stress acting upon the glide plane {111} may be calculated, considering the change in orientation of this plane relative to the growth axis during twinning. Table 2 gives data on the change in orientation of the (111) planes after twinning for the three main directions of growth. Calculation of the tangential stresses of tan led to the following result:

Card 2/6

<ul> <li>A service orange of the service of the</li></ul>	the second secon		89298	
Twins and dislocation	ons in silicon.	•	S/181/61/003/001/039/042 B102/B204	
Orientation of the original crystal	$\begin{cases} \text{tan} & \text{with res} \\ \{111\} & \text{(in B)} \end{cases}$	eat to	Angle between twinning plane and pulling axis	
[100]	main orystal	twin 2.22 1.68	0° (parallel)	
[110]	1.88	2.37	54 <sup>0</sup> 44'	, X <sup>5</sup>
[111]	1.89	1.89 3.44	90° 19°281	
n the twin depends (islocations which persons the crystal, and b) the	on two essential	l factors:	P - axial load, A - cross- hat the dislocation density a) The concentration of ard the twin from the main g system in the crystal direction of the main	29 24

· · · · · · · · · · · · · · · · · · ·	Twins and di	slocations in	n silicon			298 81/61/00 2/8204	3/001/03	9/042	X
	temperature 5 figures, 3 bloc.	gradient duri tables, and	ing the growt 4 references	h of th	ne main c oviet-blo	rystal. o and 2	There a non-Sori	re et-	ر '٠
	SUBMITTED:	January 9,	1960 Направление	CTOR (III) HACCEC- UNCAG	YFOA BACCHO- CYCR (111) G D	D Босье двой- никозания	Число плоско- стей (111) в Авойнике	YFOA MAGGEO- evek (111) o D	
			[100]	4	95°16′	[221]	1 2 1	35°16′ 11°06′ 74°12′	
			[110]	2	0° 54°44′	[110] {	2 2 1 2	0° 54°44′ 15°48′ 33°00′ 54°44′	:: ::01
			[111]	3	.90° 19°28′	[111] {	3 1	17°28' 90°00' 19°28'	i a
	Card 4/6				. 7	able2	î	33°45′ 53°06′	

#### CIA-RDP86-00513R000928910004-8 "APPROVED FOR RELEASE: 03/13/2001

211180

\$/126/61/011/006/006/011

E073/E435

AUTHORS:

Milividskiy, M.G. and Layner, L.V.

TITLE

Microhardness and Dislocation Density in Silicon

Single Crystals

PERIODICAL: Fizika metallov i metallovedeniye, 1961, Vol.11. No.6,

pp. 923-926

The micrchardness of a crystal depends not only on TEXT. individual dislocations but on the collective behaviour of larger conglomerations of such dislocations, i.e. it depends on the mutual distribution and the interaction of dislocations. Therefore, a direct correlation can be anticipated between the hardness and the density of dislocations on a given section of a crystal. The microhardness was measured on various crystallographic planes of single crystals drawn from the as It in vacuum according to the method of Czochralsky. mi iphardness depends on the method of preparing the surface of the specimens for measurements. After grinding, the

mi:rohardness H amounted to 1670 kg/mm<sup>2</sup>. By chemical polishing in an acid mixture of HF:HNO3 (1:2) for 2 to 3 min, the

Card 1/4

CIA-RDP86-00513R000928910004-8" APPROVED FOR RELEASE: 03/13/2001

### "APPROVED FOR RELEASE: 03/13/2001 C

CIA-RDP86-00513R000928910004-8

2hh80 \$/126/61/011/006/006/011 E073/E435

Microhardness and Dislocation ...

surface layer which was internally stressed by grinding was removed; then the microhardness was 950 kg/mm<sup>2</sup>. were obtained from natural cleavages of the specimen and therefore chemical polishing can be considered as the most suitable method of preparing the specimen surface for measurements. The density of the dislocations was determined on the basis of the cavities formed during etching in the mixture  $HF_3HNO_{33}(CH_3CO)_2O(1:3:3)$  for 25 to 30 minutes. Simultaneously, for some specimens, the specific resistance and the lifetime of the non-basic current-carriers were determined. dependence of the microhardness in plane (111) on the density of the dislocations in silicon single crystals is plotted in Fig.l. The increase in microhardness is particularly pronounced if the dislocation density changes within the limits of 1 x  $10^3$  to 2 x  $10^4$  cm<sup>-2</sup>; this results in an increase in the microhardness from 830 to 1250  $kg/min^2$ . Outside this range the microhardness changes much less. The changes in microhardness along the planes (110) and (100) are also fully in correlation with the distribution of the dislocation Card 2/4

THE COMPANY STREET, ST

21:1:30

S/126/61/011/006/006/011 E075/E335

Microhardness and Dislocation ....

densities; regardless of the crystallographic orientation, the maximum microhardness was always observed at the edges of the specimen and the minimum in its central part. Usually, sections with increased microhardness show a shorter lifetime of the minority current-carriers. It was established that a correlation exists between the microhardness and the density of dislocations in various crystallographic planes of silicon single crystals. The anisotropy in the microhardness of silicon single crystals drawn from the melt is determined by the general distribution of the dislocations along the crystal which is associated primarily with the thermal conditions pertaining during the growing of the crystal. Acknowledgments are expressed to D.B. Kiseleva for her assistance in carrying out the experiments.

There are 2 figures, 1 table and 15 references: 4 Soviet and 9 non-Soviet. The four latest English-language references quoted are: Ref. 6 - Wolf, G.A., Toman, L., Field, N.J. and Clark, J.C. Semiconductors and Phosphors, New Jersey, 1958; Ref. 10 - Dash, W. - Appl. Phys., 1959, 30, No. 4, 459;

Card 3/4

 $\neq$ 

21,480

\$/126/61/011/006/006/011

Microhardness and Dislocation .... E073/E335

Ref. 12 - Roberts, D.. Stephens, P. and Hunt, P. Nature, 1957, 180, No. 4587, 665; Ref. 13 - Green, G., Hogarth, C. and Johnson, F. J. Electron, and Control, 1957, 3, No. 2, 171.

ASSOCIATION: Nauchno-issledovatel'skiy i proyektnyy institut

redkometallicheskoy promyshlennosti (Scientific Research and Design Institute of the Rare Metals

Industry)

SUBMITTED: August 12, 1960

Card 4/4

5/032/62/028/004/007/026 B101/B113

AUTHORS:

Mil'vidskiy, M. G., and Layner, L. V.

TITLE:

Method of detecting dislocations in Si single crystals

PERIODICAL: Zavodskaya laboratoriya, v. 28, no. 4, 1962, 459-462

TEXT: To make dislocations in Si single crystals apparent, a 15-25 min thermal treatment of the crystals at 850-900°C in vacuo (  $\sim\!1\cdot10^{-5}~\text{mm Hg})$ and cooling at a rate of  $\sim 40^{\circ} \text{C/min}$  is suggested. The decorating of dislocations with copper in H2 atmosphere is even more efficient. The tests were made with n-type and p-type single crystals prepared by Chokhral'skiy's method. Before thermal treatment, the specimens were ground with boron carbide and M14 (M14) powder. After thermal treatment, they were polished in acid  $\angle P - 8$  (SR-8) mixture and etched in HF: HNO<sub>3</sub>:  $(CH_3CO)_2O = 1:3::3$ . The pits were counted with an MVM-8M (MIM-8M) metallographic microscope. It was found that the thermal treatment did not change density and position

Card 1/2

CIA-RDP86-00513R000928910004-8" APPROVED FOR RELEASE: 03/13/2001

S/032/62/028/004/007/026 B101/B113

Method of detecting ...

of the dislocations. The form of the etched figures observed depended on the heat treatment and on the decorating method. Dendritic inhomogeneities and stratified distribution of impurities were observed. The thermal pretreatment increases the sensitivity of chemical etching as well as the possibility of metallographically detecting inhomogeneities. There are 5 figures and 4 references: 1 Soviet and 3 non-Soviet. The three references to English-language publications read as follows: R. A. Logan, A. J. Peters. J. Appl. Phys., 28, 2, 1419 (1957); W. Dash. J. Appl. Phys., 27, 10, 1193 (1956); W. Dash. J. Appl. Phys., 30, 459 (1959).

ASSOCIATION: Gosudarstvennyy nauchno-issledovatel'skiy institut redkometallicheskoy promyshlennosti (State Scientific Research Institute of the Rare Metals Industry)

Card 2/2

TUROVSKIY, B.M.; LAYNER, L.V.

Detection of dislocations in silicon single crystals with low density dislocations. Zav.lab. 29 no.11:1331-1333 '63.

(MIRA 16:12)

1. Gosudarstvennyy nauchno-issledovatel'skiy i proyektnyy institut redkometallicheskoy promyshlennosti.

s/0070/64/009/001/0092/0097

ACCESSION NO: AP4012279

TITLE: Formation and structure of 90 degree twins in single crystals of silicon AUTHORS: Turovskiy, B. M.; Layver, L. V. grown by the Czochralski method

SOURCE: Kristallografiya, v. 9, no. 1, 1964, 92-97

TOPIC TAGS: silicon crystal, twin crystal, 90 degree twin crystal, crystal

structure, Czochralski method

ABSTRACT: The formation of 90-degree twins takes place by deviation of the growth direction from the [111] axis and is due to asymmetry in the thermal field or to disorientation of the seed crystal, Or to a combination of these two factors. The transition from clear faces to indistinct faces during twin growth is accompanied by the formation of twin laminae of adjustment. Etcn tests show that a zone with dendritic structure occurs immediately next the face of a 90-degree twin. X-ray studies indicate no deviation from monocrystalline structure, however. The most likely cause of the dendritic structure is local super-cooling, which may occur in the Czochralski method because of asymmetry in the thermal field (which is one of

Card 1/2

CIA-RDP86-00513R000928910004-8" **APPROVED FOR RELEASE: 03/13/2001** 

ACCESSION NO: AP4012279

the causes for development of the 90-degree twin growth). Orig. art. has: 8

ASSOCIATION: Nauchno-issledovatel'skiy i proyektny\*y institut redkometallicheskoy promy\*shlemmosti (Scientific Research and Planning Institute of the Rare Metal

SUBMITTED: 14Feb63

DATE ACQ: 19Feb64

ENCL: 00

SUB CODE: PH

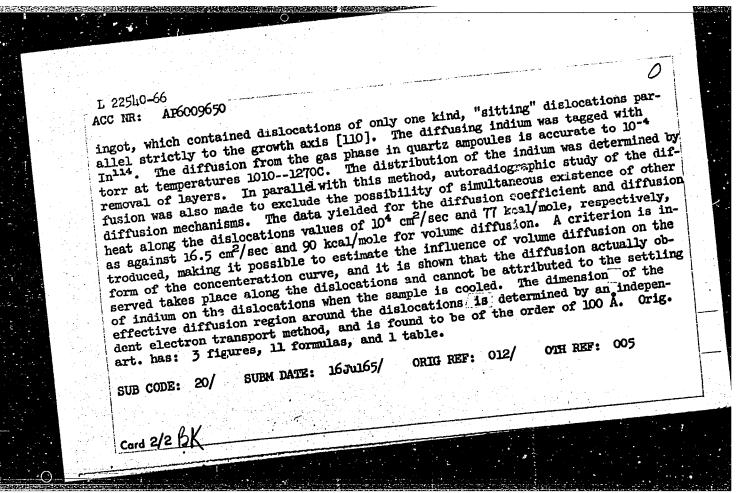
NO REF SOV: 003

OTHER: 002

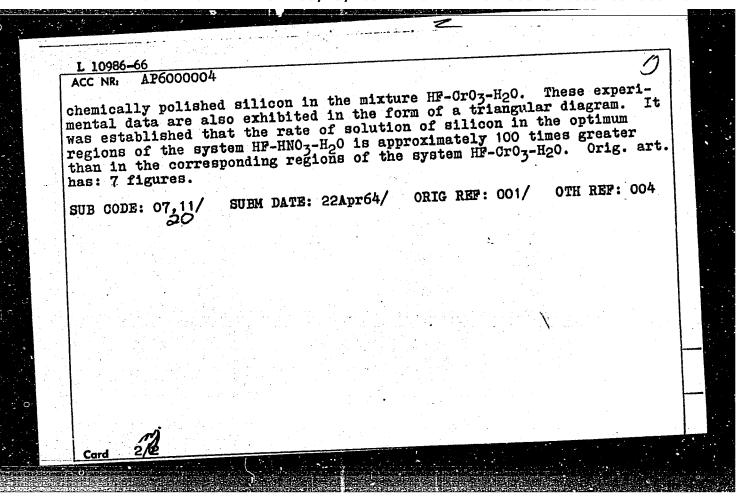
53573-65 EMA(c)/EFT(m)/EFP(b)/T/EMA(d)/EFP(	w)/EMP(t) IJP(c) JD UR/0363/65/001/003/0311/0315
ACCESSION NR: AP5011922	Layner, L. V.; Mil'vidskiy, M. G.
AUTHOR: Iglitsyn, n. 1.,  TITLE: Some characteristics of the behavior  SOURCE: AN SSSR. Izvestiya. Neorganichesk	or silicon darms
TOPIC TAGS: silicon, single crystal, therm defect, crystal impurity  ABSTRACT: The effect which thermal treatme for 10 to 90 hours) has on specific resistal principal current carriers was studied. Not wacuum and inert atmosphere with various contents was a studied. The density of lattice defects in to 1.104 per cm². The Hall effect was used ity of the current carriers. Specific resistation single crystals increases with the postulated that during thermal treatment a present in silicon single crystals with respectively.	nt of silicon monocrystals (at 1000°C nce, concentration and the mobility of and p-silicon crystals were grown in incentrations of oxygen by the Czochralski these single crystals varied from zero i as a measure of concentration and mobilistance of both n- and p-type samples of duration of the thermal treatment. It is
Card 1/2	

63573-65			$\circ$
ACCESSION NR: AP5011922  charged or neutral complexes.  charge is different in p- and  results in an increase in resi	In the case of electrically continuous in the case of electrically continuous interest in the case of electrically continuous interest in the continuous c	lity of the curr	s their eatment cent duration
carriers in both n- and p-type of the thermal treatment. Ori	ig. art. has: 1 table, 4 figur	es, and 1 formu	la.
SUBMITTED: 090ct64	ENCL: 00	SUB CODE:	
NO REF SOV: 000	OTHER: 007		
		# # P P P P P P P P P P P P P P P P P P	iku urbii rini

L 22540-66 EWT(1)/EWT(m)/T/EWP(t) IJP(c) JD/GG SOURCE CODE: UR/0181/66/008/003/0725/0730 ACC NR: AP6009650 AUTHOR: Pavlov, P. V.; Layner, L. V.; Sterkhov, V. A.; Panteleyev, V. A. ORG: Gor'kiy State University im. N. I. Lobachevsiy (Gor'kovskiy gosudarstvennyy universitet) TITLE: On the proof of the existence of an autonomous diffusion flux along inolated dislocations SOURCE: Fizika tverdogo tela, v. 8, no. 3, 1966, 725-730 TOPIC TAGS: crystal lattice dislocation, physical diffusion, silicon, single crystal ABSTRACT: This is a continuation of earlier work by the authors (FTT v. 7, 922, 1965 and v. 6, 384, 1964), where it was shown that diffusion along dislocations exist in single crystals of germanium and silicon, in addition to the ordinary volume diffusion. Since these results differ from those of many others, the authors present, using the diffusion of indium in silicon as an example, new results to confirm that the diffusion along the dislocations is much faster than through the volume. The investigations were made on "sitting" dislocations. p-type silicon samples were used, with specific resistivity 18 ohm-cm and average dislocation density  $N_d = 10^4$  cm<sup>-2</sup>. The samples were cut from a specially grown Card 1/2



L 10986-66 ENT(m)/T/EWP(t)/EWP(b)/EWA(g) IJP(c) UR/0080/65/038/011/2473/2475 AP6000004 ACC NR: AUTHOR: Layner, L.V.; Layner, V.I.; Baronova, Z.A. TITLE: Chemical polishing and etching of single silicon srystals for ORG: None exposure of dislocations SOURCE: Zhurnal prikladnoy khimii, v.38, no.11, 1965, 2473-2479 TOPIC TAGS: crystal dislocation, silicon single crystal, metallography ABSTRACT: Two ternary systems were investigated in the experiments: HF-HNO3-H20 and HF-Cro3-H20. The system HF-HNO3-H20 was used to establish the optimum region for the polishing of a silicon single crystal, and the system, HF-Cr03-H20 for the optimum region for etching to expose and the system of the effect of concentration of individual components of the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system on the quality of the polished surface was determined by the HF-HN03-H20 system of the HF-HN03mined by setting up a triangular concentration diagram. The diagram was constructed with data from the study of 230 tested solutions and is given in the article. A figure shows the dependence of the rate of solution of silicon with an increase in the concentration of HNO3 and the decrease in the concentration of HF with a varying amount of added water For exposure of dislocations, the authors studied the etching of UDO: 621.357.8 + 621.315.592 1/2



LAYNER, M.

27-11-10/31

AUTHOR: Layner, M., Instructor at Construction School # 7, Kiyev

TITLE: Training of Concrete Workers (Podgotovka betonshchikov)

PERIODICAL: Professional'no - Tekhnicheskoye Obrazovaniye, 1957, # 11,

p 14-15 (USSR)

ABSTRACT: The article contains particulars on the theoretical instruction

of concrete-reinforcement workers at the Construction School # 7, Kiyev (Stroitel'naya shkola # 7, Kiyev). The students are required to pass special courses in technology and knowledge of materials. In general it provides for the study of advanced methods of labor and of the latest techniques in performing reinforcement and concrete work. How the training is conducted is described by a few examples, such as information on the parts of a building and the order of carrying out construction work; straightening and sorting of the steel rods, the drawing out and cutting of the wire rod; and electrical butt welding. On one occasion the students were shown an entirely new device - a multiple point welding machine "BHMCTO" for welding screens

up to 2,5 m length.
ASSOCIATION: Construction School # 7, Kiyev (Stroitel'naya shkola # 7, Kiyev)

Card 1/1

IAYNER, S., starshiy nauchnyy sotrudnik; LIMONOV, E., starshiy inzh.

Criteria and economic indices of seagoing freighter efficiency. Mor.flot. 20 no.8:3-6 Ag 160.

(MIRA 13:8)

1. TSentral'nyy nauchno-issledovatel'skiy institut morskogo flota.

(Freighters-Cost of operation)
(Ocean liners-Cost of operation)

VOLCHEK, N., nauchnyy sotrudnik; LAYNER, S., nauchnyy sotrudnik;
LIMONOV, E., nauchnyy sotrudnik

Dry-cargo liner fleet of capitalist countries of Europe. Mor.
flot 22 no.4:38-39 Ap '62. (MIRA 15:4)

1. TSentral'nyy nauchno-issledovatel'skiy institut morskogo flota.
(Europe-Freighters)

LAYNER, S., kand.tekhn.nauk, starshiy nauchnyy sotrudnik

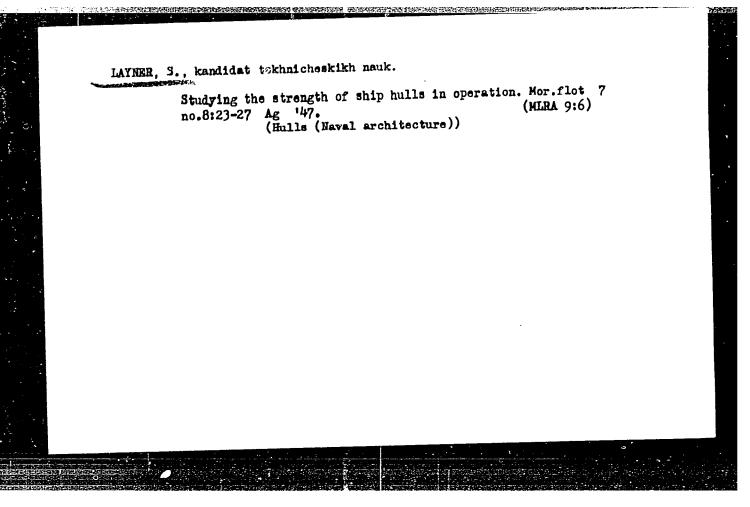
Method of comparative evaluation of the operational and technical efficiency of freighters. Mor. flot 22 no.8:35-36 Ag '62. (MIRA 15:7)

1. TSentral'nyy nauchno-issledovatel'skiy institut morskogo flota.

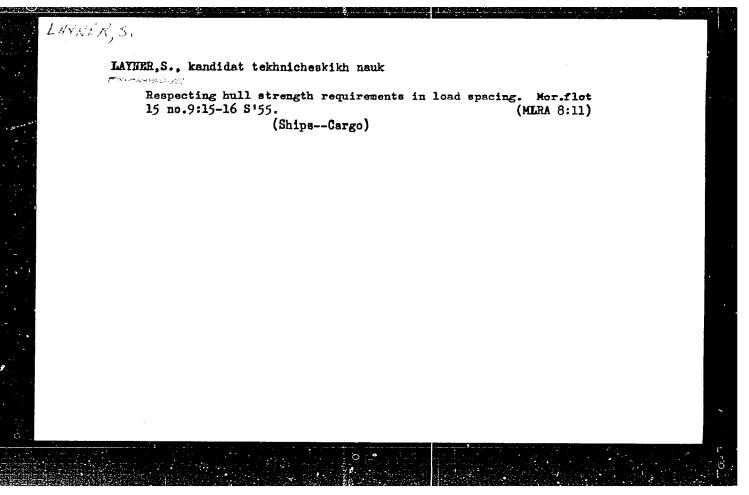
(Freighters)

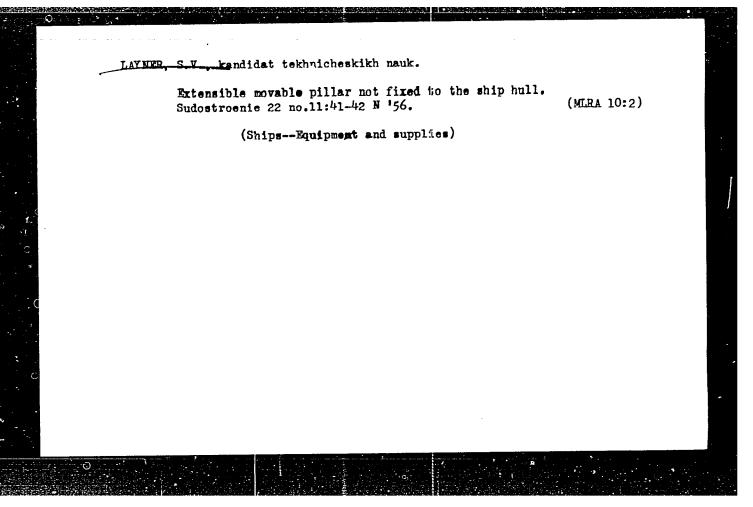
FA 30T85 LAYNER, S. V. Jan 1946 UESR/Ships, Cargo Ships, Construction "The Demands of Cargo-passenger Ships of the Far Eastern Line, S. V. Layner, Candidate in Technical Sciences, 42 pp "Morskoy Flot" No 1 The planning of new types of ships for the far eastern area must consider the experiences of the ships of the "Sakhalin" and "Anadyr" types which were built in 1929 - 1933. The article discusses the structure of the hull, general plan and internal structure of passenger and service spaces, cargo accommodations, and engineering considerations for the new ships.

LAYNER, S.	PA 16T8	
	•-	
	USSR/Ships - Construction Jul/Aug 1946 Ships, Welded	
	"Desirable Changes and Additions to Regulations for the Classification and Construction of Steel Seagoing Vessels'," S. Layner, 6 pp	
	"Mor Flot" No 7/8	
	Welded construction, determination of measurements of ship ribs, new types of cargo and passenger-cargo vessels, construction of hulls of tenkers, increase of thickness of bulkheads in cargo holds, etc., are among the desirable changes recommended.	
	16Т8	



LAYNER, S. PA 61769 USSR/Engineering Mar 1948 Ships, Passenger Ships - Specifications "Requirements for Passenger Vessels on the Crimea-Caucasus Line, "S. Layner, Cardidate Tech Sci, 4 pp "Morsk Flot" No 3 New vessels are based on design of vessels now plying subject route, including "Krym," "Gruziya," "Adzharis-tan," "Abkhaziya," etc. Vessels now in design stage will be 1,100 meters along water line, beam about 18 meters, 6 meters draught when empty; speed 11-12 knots, with a capacity for 1,000 tons of cargo; capable of carrying about 900 passengers comfortably. These boats will be known as "Krymchak" type.

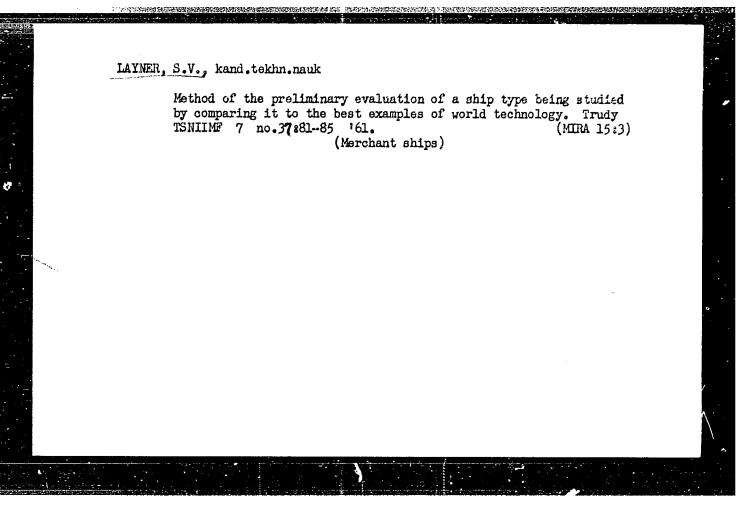




IAYMER. Samil Vladimirovich; GORYANSKIY, Yu.V., otvetstvennyy red.; SHISHKOVA,
I.M., tekhn.red.

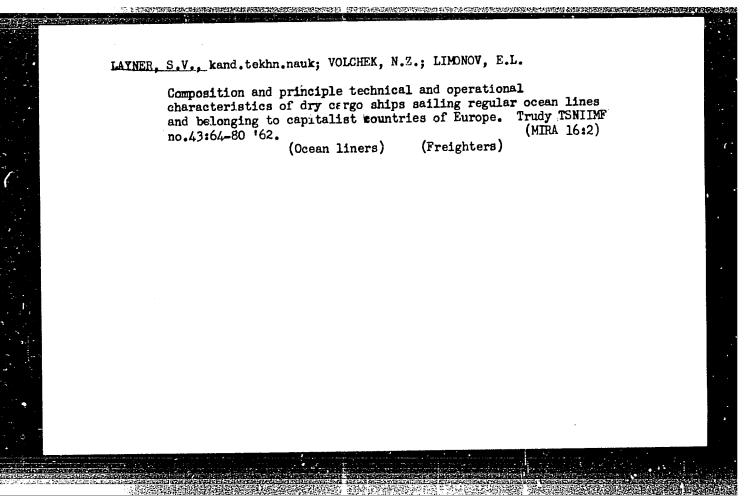
[Seegoing dry cargo vessels] Morskie sukhogruznye suda. Leningrad,
Gos. izd-vo sudostroit. lit-ry, 1957. 283 p. (MIRA 11:5)

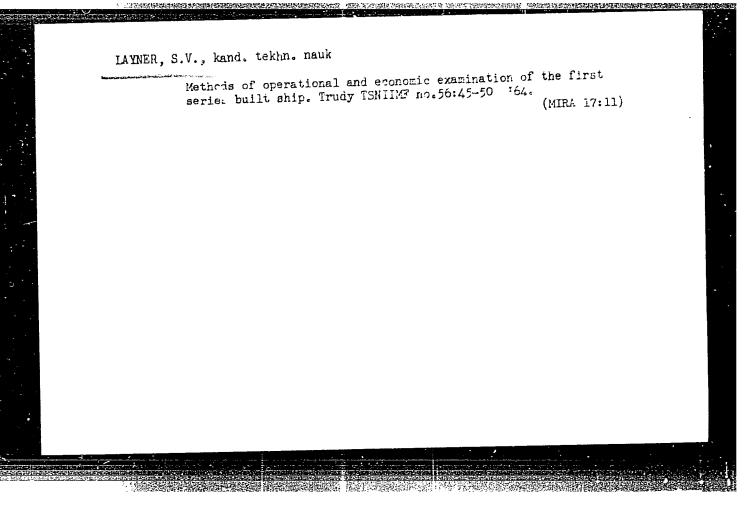
(Freighters)

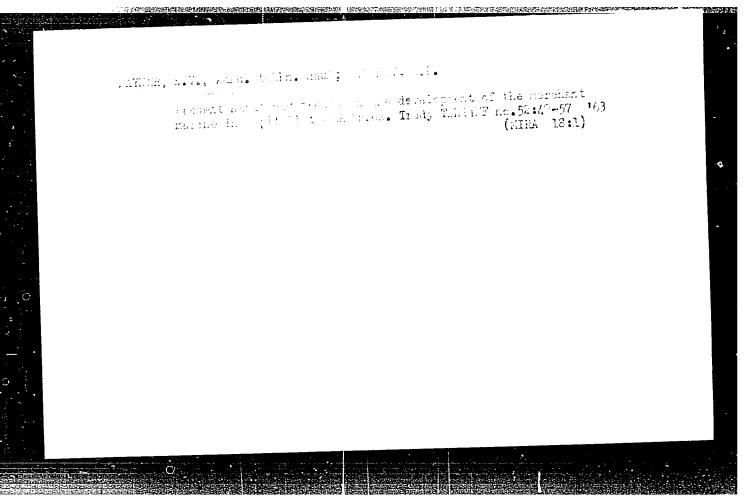


LAYNER, S.V., kend.tekhn.nauk; LIMONOV, E.L.

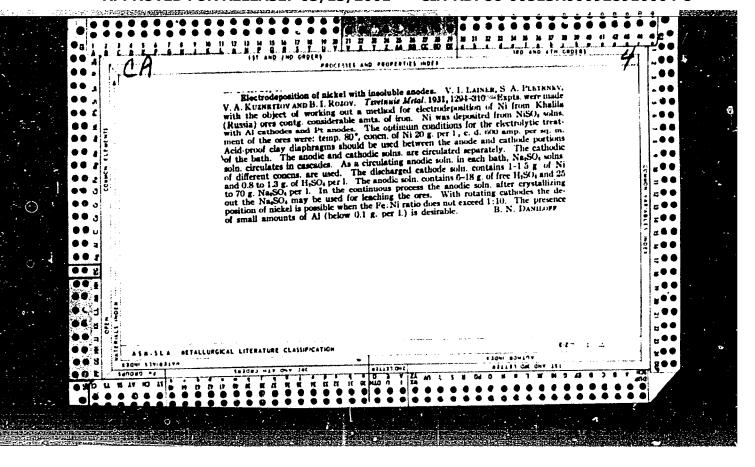
Methods of economic justification for selecting the optimum variant of a sea transportation ship. Trudy TSNIIMF no.29:62-68 '60. (MIRA 15:11) (Marchant marine—Gost of operation) (Ocean liners)

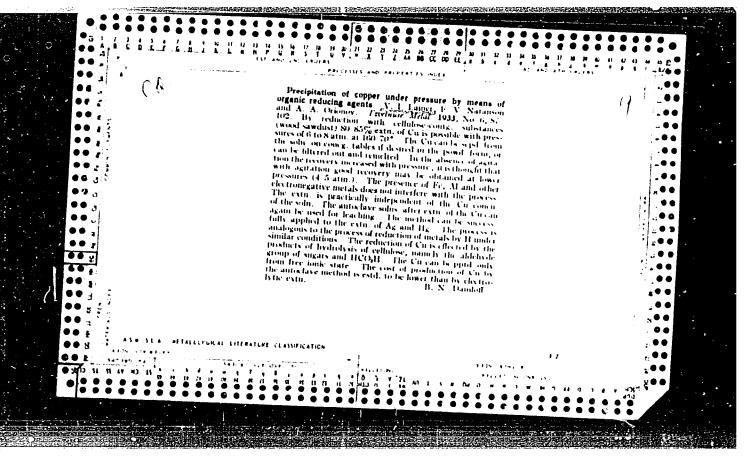


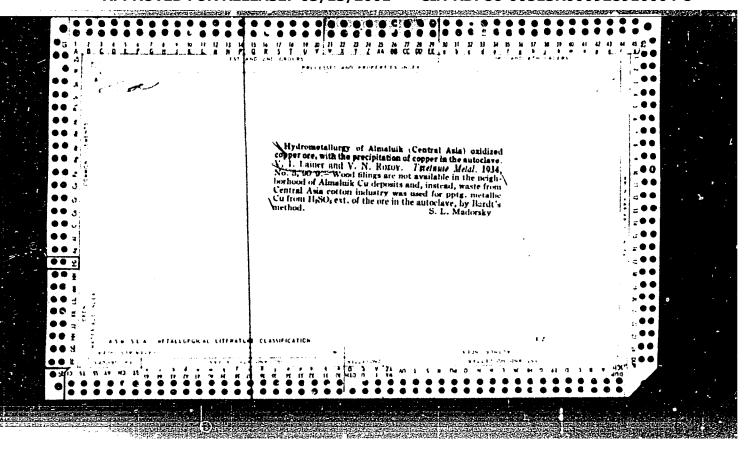


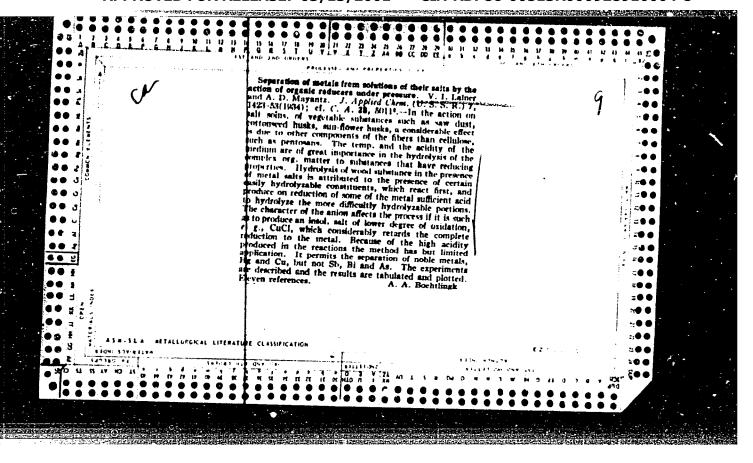


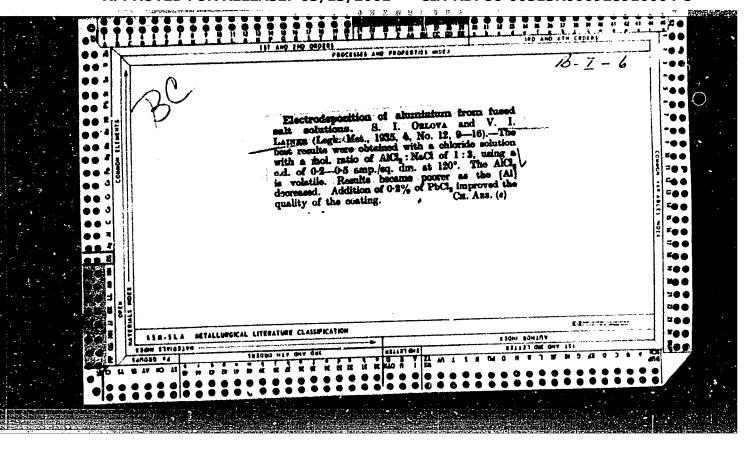
APPROVED FOR RELEASE: 03/13/2001 CIA-RDP86-00513R000928910004-8"



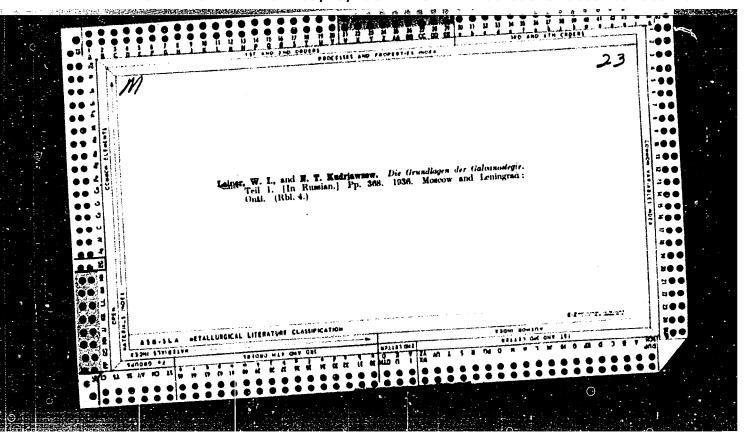


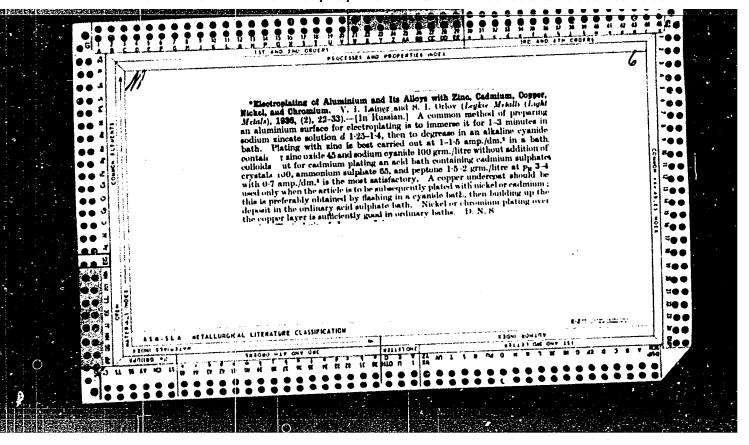


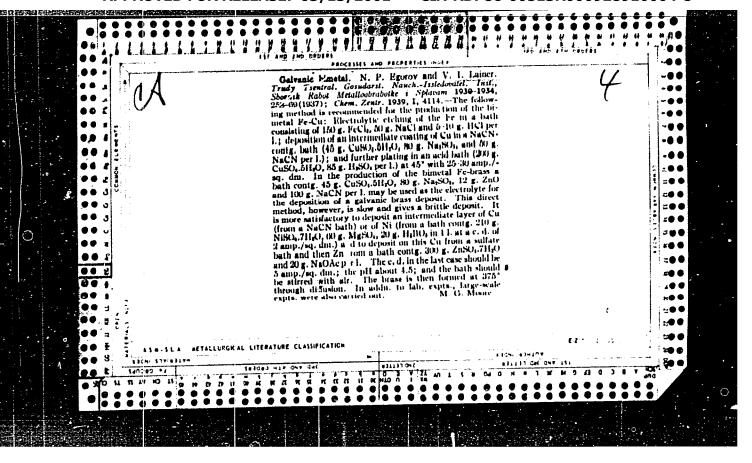


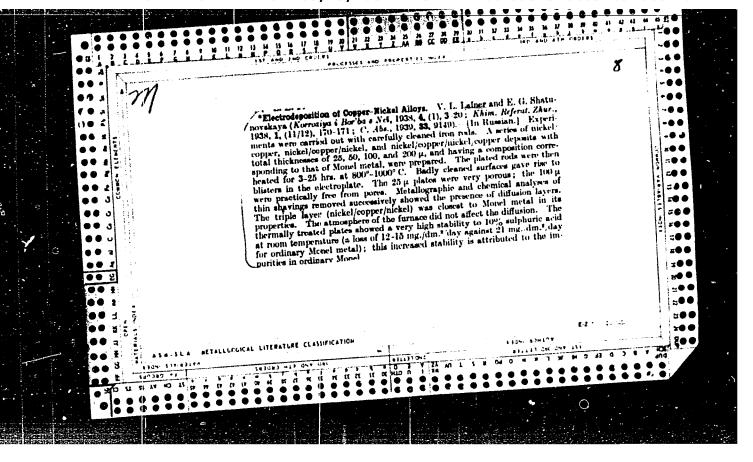


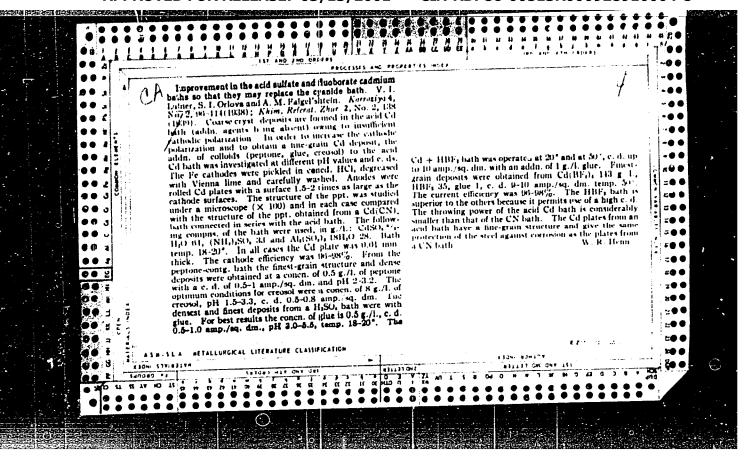
"APPROVED FOR RELEASE: 03/13/2001 CIA-RDP86-00513R000928910004-8

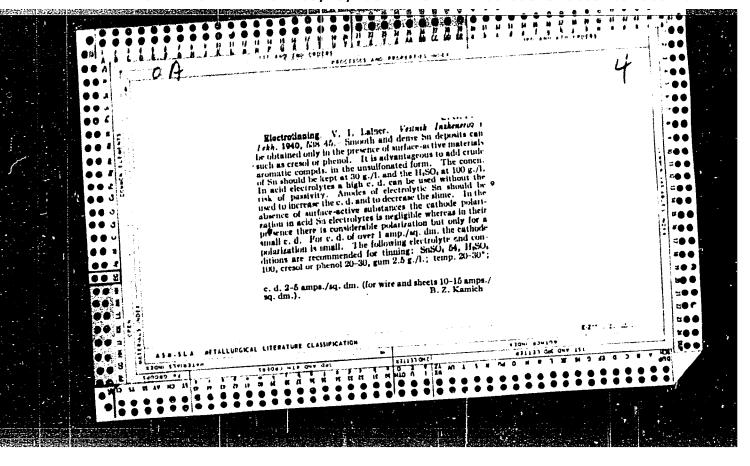


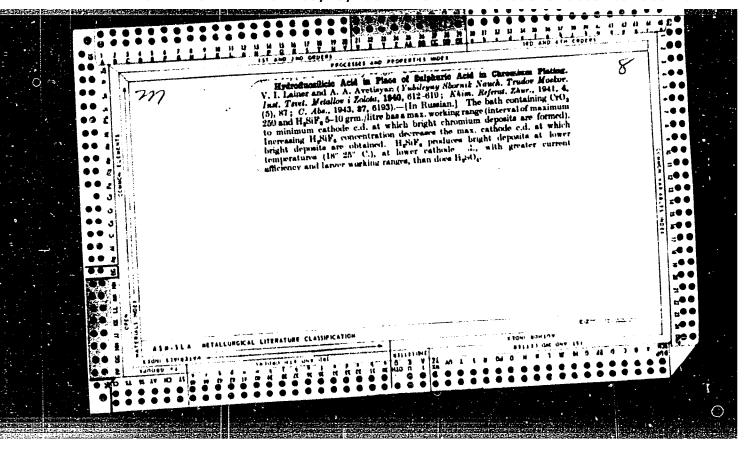


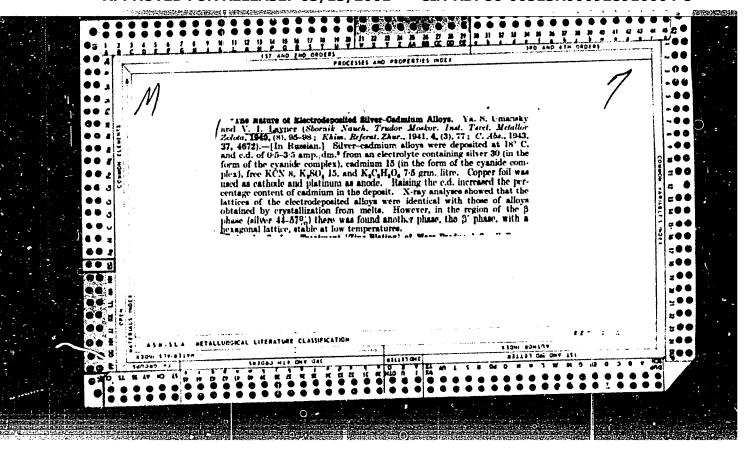


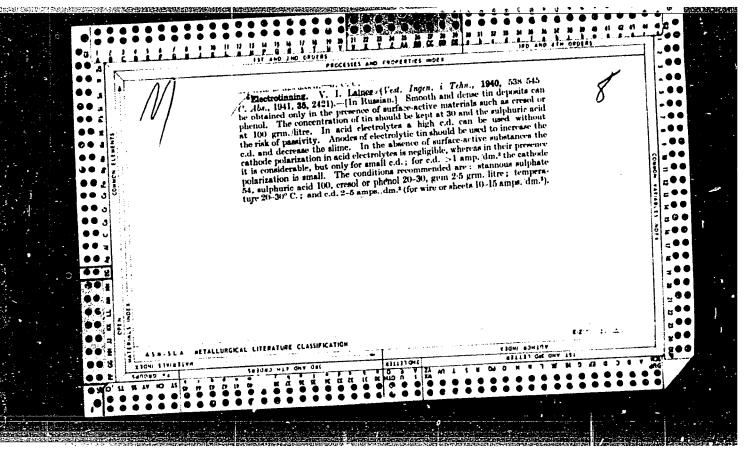


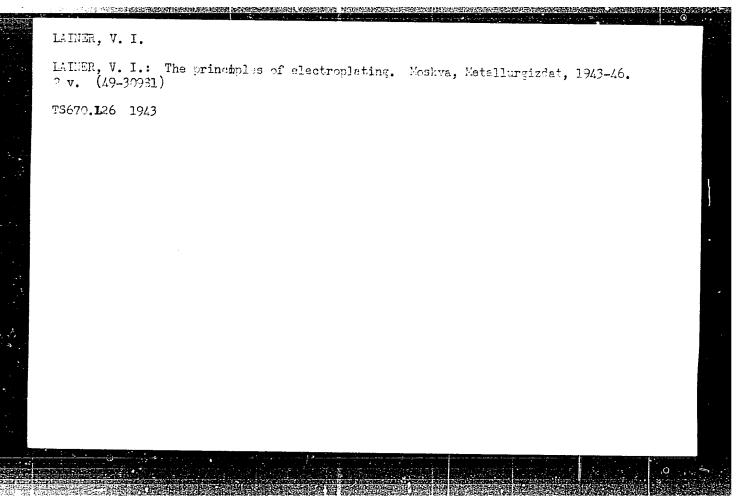


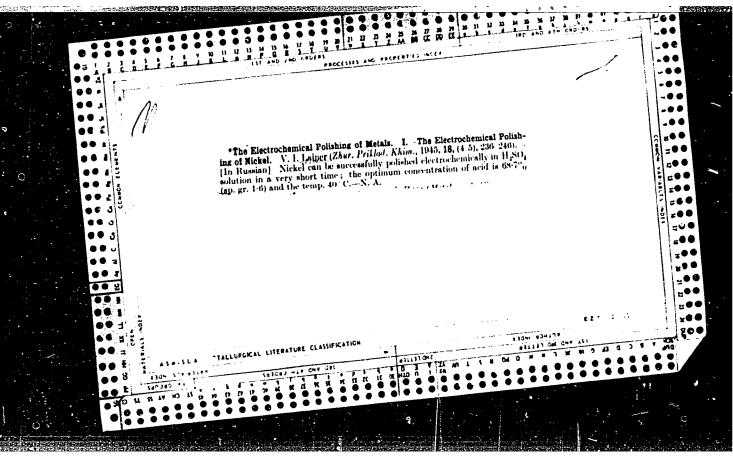


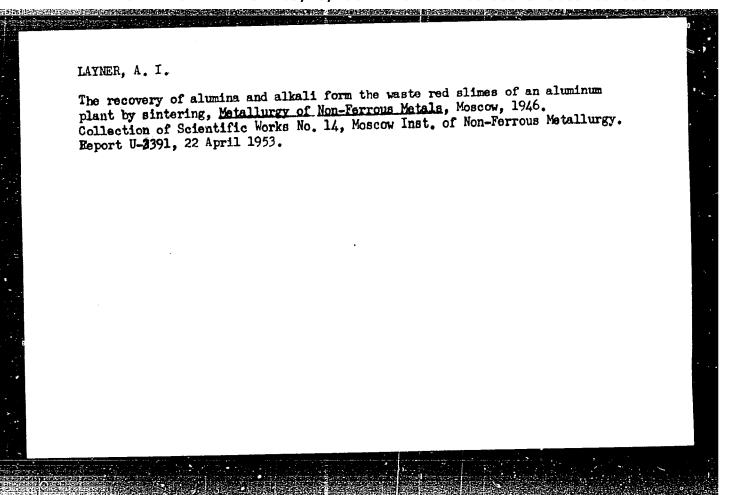


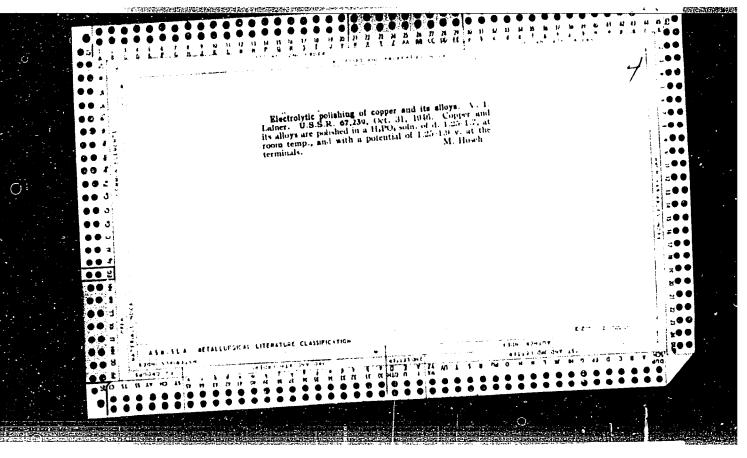


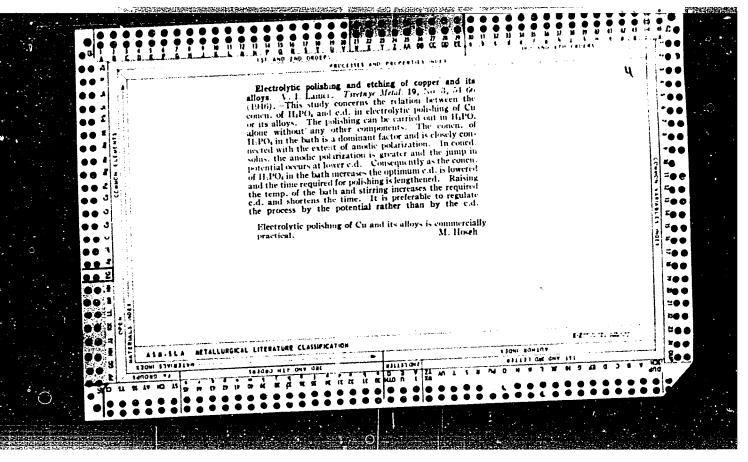


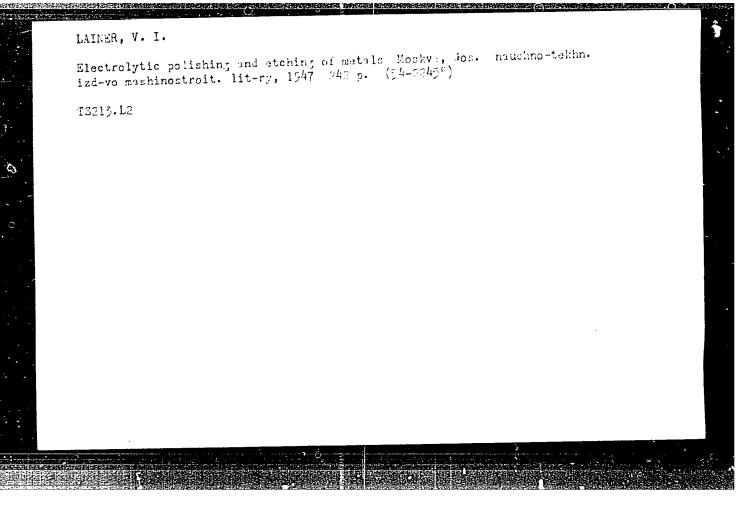


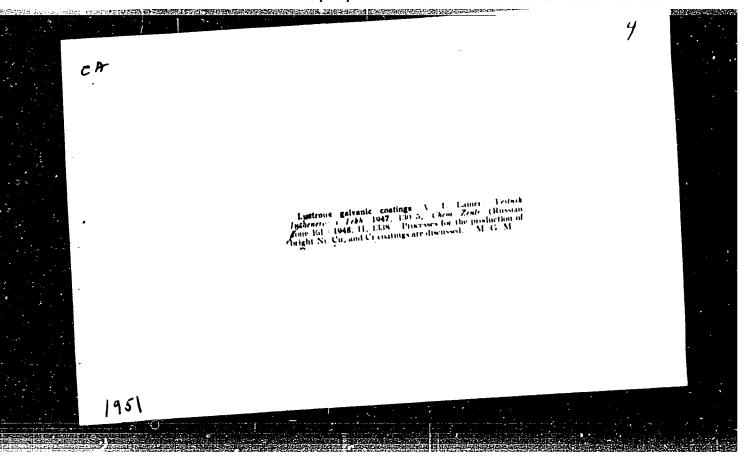












"思想这"不过的明朝中代				HILLEN E		ध्यानका अस्तर क	*******	 	-1-07		Masters.
Li	YNER, V. I.	deal.	"Erricient Methods for Obtsining Shiny Gelvanized Plating," Frof V. I. Layner, Dr of Technical Sciences, Deputy Chairman for the Committee on Gelvenizing for VSHITO, 6 pp	leith" No 4 se pitting in nickel	prenomentaly supply of electronic supply of electronic supply of the sup	(Contd) Apr 1947	A people must be trained for its efficient Prequent reference is made to electrolyte ing methods used in the US.	<b>P</b> *	0) = 0.7	24167	
		USER/Metals Gelvanising Plating, Mickel	"Esting," Prof V. I. Deputy Chairman for VEBRITO, 6 Pp	"Yest Inzher 1 Tekh" No 4	plate, as well as the use of perions ze. Mickel plating far the most efficient	UBER/Metals (Co	however, and people must operation. Frequent renieds				

Layner,	V. I.	IA 12T69	0
	USSR/Gelvanizing Apr 1	947	
	Zinc coatings  "The Problem of an Economical Method of Shiny		
	Galvanizing, V. I. Layner, 6 pp "Vestnik Inzhenerov i Tekhnikov" Vol XXXII, No	4	
	Cives microphotos of flaws in the zinc covering Discusses electrolytic polishing.	•	
	12:	169	
		····	
		Manufacture and an experience of the second	

USER/Metals Jul/Aug 48 Pickling (Metals)	
"Electrolytic Pickling of Metals," V. I. Layner, Prof, Dr Tech Sci, Deputy Rep for Committee of Galvanostegy, VSNITO, $6\frac{1}{4}$ pp	
"Vest Inzhener i Tekhnik" No 4	
Lists disadvantages of chemical method of pickling.  Describes various types of electrochemical pickling.  Graphs show time required varies with current density, temperature and chemical concentration.	
10/49188	

#### CIA-RDP86-00513R000928910004-8 "APPROVED FOR RELEASE: 03/13/2001

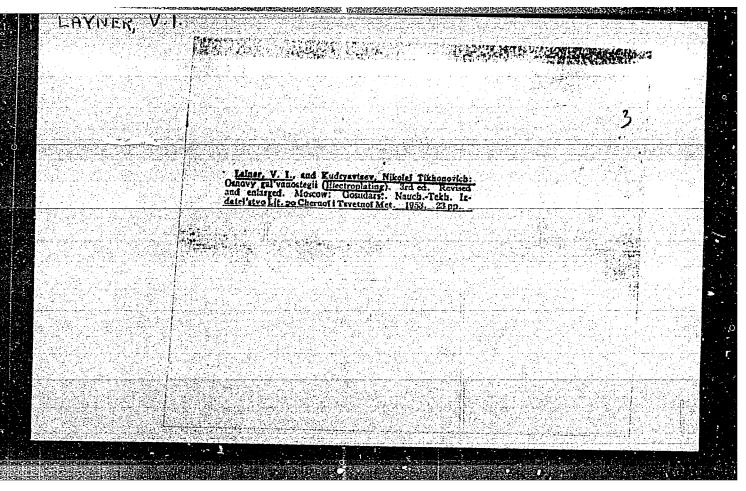
Layner, V. I.

Technology

(Corrosion and protection of metals) Moskva Gos. nauchno-tekhn. izd-vo ļit-ry po chernoi i tsvetnoi metallurgii 1.951 Pt. 4 (Metal coatings, electro-chemical and chemical treatment of metals)

Monthly List of Russian Accessions, Library of Congress, July 1952. Unclassified.

"APPROVED FOR RELEASE: 03/13/2001 CIA-RDP86-00513R000928910004-8



AND AND THE PROPERTY OF THE PR LAYNER V.I.

· PHASE I

TREASURE ISLAND BIBLIOGRAPHICAL REPORT

AID 587 - I

BOOK

Authors: LAYNER, v. I. and KUDRYAVTSEV, N. T. Call No.: AF639674 Full Title: FUNDAMENTALS OF ELECTROPLATING. Part 1, 3rd. ed.rev. Transliterated Title: Osnovy gal'vanostegii. Chast' 1. 3-e izd., perer. i dopol.

PUBLISHING DATA

Originating Agency: None

Publishing House: State Scientific and Technical Publishing House of Literature on Ferrous and Nonferrous Metallurgy (Metallurgizdat) te: 1953 No. pp.: 624 No. of copies: 15,000 Date:

Editorial Staff

Appraiser: Titov, P. S., Prof. Dr.
PURPOSE: The book is intended for engineers and technicians in scientific research institutions, enterprises and design organizations dealing with problems of corrosion and electroplating, and can be useful to students specializing in this field. TEXT DATA .

Coverage: This work deals with the general principles and the technology of electroplating processes, as well as with the processes of the preparation of metal surfaces for the application of metal layers. It gives the characteristics of metal coatings and discusses

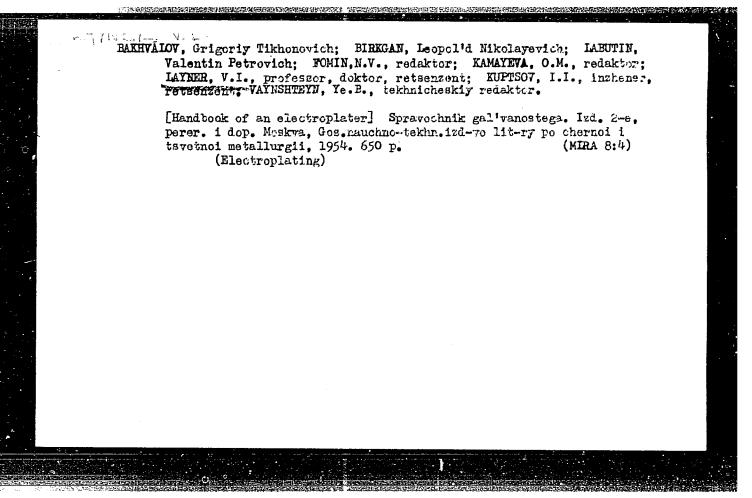
1/2

. Osnovy gal'vanostegii. Chast' l. 3-e izd., perer. i dopol. AID 587 - I

the quality of electrolytic platings as it depends on the surface conditions and on the plating materials. The book describes the surface treatment, the electrolytic polishing of metals, the structure of the deposited metals and the metal distribution in a cathode surface. Zinc, cadmium, copper, brass, nickel, chromium, tin and lead plating processes are examined in detail, with attention to the qualities, corrosion-resisting properties and the practical application of different coatings. This work is the third supplemented edition. Some chapters are radically changed and new chapters are added. The book is provided with illustrations, microphotographs of surfaces, tables and diagrams.

No. of References: Total 167, Russian 160, 1909-1952. Facilities: B. S. Yakobi, E. K. Lents, P. P. Fedot'yev, V. A. Kistyakovskiy, N. A. Izgaryshev

2/2



```
LAYNER VI. BAZHENOV, M.F.; BAKHVALOV, G.T.; BEZALDEEMKO, N.P.; BERMAN,S.1.;

BOGDANOV, Ye.S.; BODYAKO, M.N.; BOYKO, B.B.; VINOGRADOV, S.V.;

GAORD-TORN, K.V.; GLEK, T.P.; GOREV, K.V.; GRADUSOV, P.I.; GUSHCHINA,T.N.;

GAORD-TORN, A.K.; YESIKOV, M.P.; ZUZTARSKIY, A.V.; ZAKHAROV, M.V.;

ZAKHAROVA, M.I.: KARCHEVSKIY, V.A.; KOMAROV, A.M.; KORZHENKO, O.T.;

ZAKHAROVA, M.I.: KARCHEVSKIY, V.A.; KOMAROV, A.M.; KORZHENKO, O.T.;

LATURE, V.I.; MALITSEV, M.V.; MILLER, L.Y.E.; MILOVANOV, A.I.;

LATURE, V.I.; MALITSEV, M.V.; DIKHOV, N.P.: OSIPOVA, T.V.;

OSOKIN, N.Y.E.; PERLIN, I.L.; PLAKSIN, I.N.: PROKOF'YEY, A.D.;

RUMYANTEKV, M.V.; SEVERIENKO, V.P.; SEREDIN, P.I.; SMIRYAGIN, A.P.;

RUMYANTEKV, M.V.; SEVERIENKO, V.P.; SEREDIN, P.I.; SMIRYAGIN, A.P.;

SHEIGHINSTSKIY, YE.S.; YURKSHTOVICH, N.A.; YUSHKOV, A.V.;

YANUSHEVICH, L.V.

Sergei Ivanovich Gubkin. TSvet.met. 28 no.6:60-61 N-D '55. (MIRA 10:11)

(Gubkin, Sergei Ivanovich, 1898-1955)
```

FEDOT'YEV, Nikolay Pavlovich; GRILIKHES, Semen Yakovlevich; LAYNER, V.I., professor, retsenzent; KHEYFETS, B.L., kandidat khimicheskith nauk, redaktor; VASIL'IEVA, V.P., redaktor izdatel'stva; POL'SKAYA, R.G., teknhinicheskiy redaktor

[Electrochemical pickling, polishing and oxidation of metals]

Blektrokhimicheskoe travlenie, polirovanie i oksidirovanie metallov. Moskva, Gos. nauchno-tekhn. izd-vo mashinostroit.

1it-ry, 1957. 242 p. (MLRA 10:5)

(Oxidation, Electrolytic) (Electrolytic polishing)

(Metals--Pickling)

Layner, Vladimir I., Professor, Dector, Kudryavtsev, Nikolay T., Osnovy gal'vanostegii (Principles of Electroplating) Chast' II Professor, Doctor. (Part II) Moscow, Gosudarstvennoye nauchno-tekhnicheskoye izdatel'stvo literatury po chernoy i tsvetnoy metallurgii, 1957, 3d edition, rev. and enl., 647 pp., 10,000 copies. Chernov, A. N.; Ed. of the Publ. House: Kamayeva, O. M., Tech., Ed.: Attopovich, M. K.; Reviewers: Gorbunova, K. M., Professor, Doctor; Dokin, N. I., Engineer, and Semin, V. M., Engineer. Ed.: The book is intended for engineers and technically trained The book is intended for engineers and technically trained personnel in electroplating shops, scientific research institutions, and engineering design organizations, and may be of use to university students. PURPOSE: card 1/16

CIA-RDP86-00513R000928910004-8" APPROVED FOR RELEASE: 03/13/2001

Principles of Electroplating (Cont.)		
COVERAGE: The book treats of electroplating with noble and rare and alloys. Equipment, theoretical principles and to niques of electroplating are described in detail. Per alities mentioned include: Shvyryayev, G. K., Engineer. There are 202 references of which are USSR, 78 English and 28 German.	ech <del>-</del>	
TABLE OF CONTENTS:		
Preface	•	
Ch. T. Eleatmoderate.	8	
Ch. I. Electrodeposition of Iron and Cobalt		
Electrodeposition of iron Use of iron plating and properties of electrodeposited	9	
iron baths	9	
Freparation, control and adjustment of electrolytes Electrodeposition of cobalt	13 21	
Ch. II. Electrodeposition of Indium	22	
Card 2/16		
· · · · · · · · · · · · · · · · · · ·		¥=

#### "APPROVED FOR RELEASE: 03/13/2001 CIA-RDP86-00513R000928910004-8 1次是全国的国际的国际的国际的国际的国际的国际国际的国际国际的国际国际的国际国际

LAYNER, V.I.

AUTHORS: Layner, V.I., Professor, Doctor and Velichko, Yu. A.,

Galvanothermic Method of Producing Steel/Copper-Zinc Alloy TITLE: Bimetal. (Gal'vanotermicheskiy metod polucheniya bimetalla

PERIODICAL: Tsvetnyye Metally, 1957, No.3, pp.60-66 (USSR)

ABSTRACT: There are practical difficulties in depositing electrolytically a copper-zinc alloy; copper and zinc, however, can be deposited separately without difficulty and this is the principle of the "galvanothermic" method of making bimetal. The zinc and copper are deposited on the steel in thin layers which diffuse into each other on annealing. The investigation of this process is described in the present article. The steel was first coated thinly with nickel and then with copper and zinc in acid electrolytes to give a total thickness of 30 or 90. µ. Annealing was carried out in a reducing atmosphere and specimens were then subjected to microscopic analysis, to chemical analysis of different layers and to deformation tests. Graphs show changes in composition with depth for specimens treated 1/2 under various conditions and photomicrographs are also shown. It was shown that under the above conditions the

Galvanothermal Method of Producing Steel/Copper-Zinc Alloy Bimetal.

zinc content decreases with increasing depth from the surface; least variation in composition was found in specimens heated for three hours at 400 C and then for four hours at 520 C. Satisfactory adhesion between copper and steel was obtained with a 1  $\mu$  thick nickel deposit. Good adhesion and stamping properties were obtained. There are 10 figures and 4 references, 2 of which are Slavic.

AVAILABLE: Library of Congress

LAYNER, V.I.

AUTHOR: Layner, V.I., Doctor of Technical Sciences, Professor, and Velichko, Yu.A.

TITLE: Copper plating in hydro-fluoric boron electrolytes. (Medbebie v borftoristovodorodnykh elektrolitakh.)

"Vestnik Mashinostroeniya" (Engineering Journal), 1957, PERIODICAL: No.4, pp. 60 - 64 (U.S.S.R.)

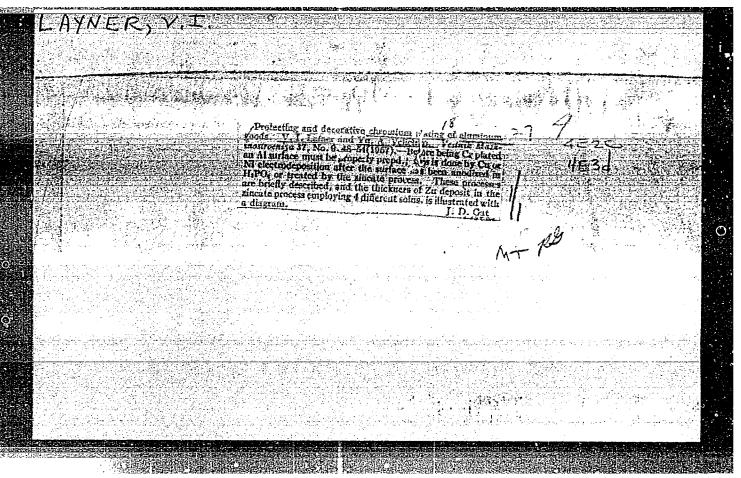
ABSTRACT: Investigations on hydro-fluoric boron electrolytes are reported containing between 17 and 125 g/litre of copper in the form of hydrofluoric boron salts. The raw materials for preparing the electrolyte were hydrofluoric acid, boric acid and copper sulphate first transformed into copper carbonate. The method of obtaining the electrolyte is described in detail. The copper content in the bath was determined by the electrolytic or the volume method. The analytical procedure is described. For all electrolytes the upper limit of the permissible current density at different temperatures was determined both at rest and when stirred by air. The porosity of coatings (depending on their thickness), the strength of the bend with the parent metal and the capacity of copper-plated steel to be deformed in press tools were found. Specimens of low carbon steel were degreased, subjected to anodic treatment in an alkaline solution and plated with a nickel undercoat of

Copper plating in hydrofluoric boron electrolytes. (Cont.)

1 μ thickness. It is not necessary to obtain a completely dense nickel coat. The copper coat forms bridges through the pores of the nickel. The solution of iron in the pores is retarded by cathodic polarisation. The adhesion strength of the copper coat was determined by repeated bending tests, by the Ericson drawing test and by annealing. Bad adhesion was obtained with a very thin (0.2 μ) or a very thick (5 μ) nickel undercoat. The tests are summarised in tables and graphs. The distinguishing feature of hydrofluoric boron electrolytes, compared with sulphates, is a much greater permissible current density. This rises with the concentration of the copper salt. At 20°C and 17 g/litre copper in the form of hydrofluoric boron salt, good deposits are obtained with a density of 2 A/dm. With a copper concentration of 125 g/litre the permissible current density rises to 25-30 A/dm. A high temperature and stirring of the electrolyte help to increase the permissible current density. In the dilute bath an increase of temperature from 20 to 65°C raises the permissible current density from 2 to 5 A/dm. Stirring by air increases the permissible from 20 to 65 A/dm. Stirring by air increases the permissible density almost two-fold. Non-porous copper coats from electrolytes of medium concentration (80 g/litre) are obtained if

Copper plating in hydrofluoric boron electrolytes. (Cont.) 30  $\mu$  thick or above. 50  $\mu$  thickness is necessary when plating from dilute baths. The coat becomes smooth at a large thickness (100  $\mu$ ). Such coats still retain good adhesion and can be recommended for producing bi-metallic strip subject to deep drawing operations.

3/3 There are 6 figures, 2 tables and 3 non-Slavic references. AVAILABLE:



AUTHORS:

Layner, V.I., Panchenko, I.I.

PRODUCTION OF THE PRODUCTION O

TITLE:

Electrode Processes in Electro-deposition of Nickel from Fluoborate Electrolytes (Elektrodnyye protsessy pri elektro-

osazhdenii nikelya iz ftorboratnykh elektrolitov)

-

Izvestiya Vysshikh Uchebnykh Zavedeniy, Tsvetnaya Metallurgiya, 1958, Nr 5, pp 124 - 130 (USSR)

ABSTRACT:

PERIODICAL:

The object of the investigation described in this paper was to study the effect of various factors on electrode-position of nickel from fluoborate solutions and on the quality of the deposits obtained by this method. For the preparation of the HBF4 solution, chemically pure

H<sub>3</sub>BO<sub>3</sub> and an HF solution (whose concentration was determined from its density) were used in the stoichiometric ratio, H<sub>3</sub>BO<sub>3</sub> being added (a small quantity at a time) to the continuously stirred and ice-cooled HF solution. To the obtained HBF<sub>4</sub> solution, also continuously cooled, nickel carbonate (a small quantity at a time) was added and in this manner it was possible to obtain solutions

containing up to 180 g/litre nickel in the form of

Cardl/8

SOV/149-58-5-14/18

Electrode Processes in Electro-deposition of Nickel from Fluoborate Electrolytes

fluoborate (density approx. 1.5), which could then be diluted to any required concentration. The characteristics of the experimental electrolytes (pH = 3 in all cases) are given in Table 1 which shows the nickel concentration (N = 1 to 4), the content (in g/litre) of fluorine,  $F_1$ , present in the form of  $BF_3OH$ , the content of fluorine,  $F_2$ , present in the form of BF4-, the total fluorine content  $\mathbf{F} = \mathbf{F}_1 + \mathbf{F}_2$  , the B content, the F/B and F/Ni ratios, the NiCl<sub>2</sub>.6H<sub>2</sub>O content, and the density at 20 °C. Nickel anodes and steel, copper or brass cathodes were used in the experiments, the results of which are reproduced graphically. The effect of the current density (A/dm²) on the cathode potential is illustrated in Figure 1, where graphs 1, 2, 3 and 4 correspond to the nickel concentrations of 1N, 2N, 3N and 4N, respectively. Figure 2 illustrates the current-density/cathode-potential Card2/8 relationship for electrolytes with no excess of HzBOz

Electrode Processes in Electro-deposition of Nickel From Fluoborate Electrolytes

(graph 1) and with 5, 10 and 15g/litre H<sub>3</sub>BO<sub>3</sub> in excess of the stoichiometric ratio (graphs 2,3 and 4). The results of the tests in which the current-density/cathode-potential relationship was studied for 3N electrolytes containing no Cl ions at 20°C and those containing 15, 30 and 50 g/litre NiCl<sub>2</sub>.6H<sub>2</sub>O at 50°C are reproduced in

Figure 3 (graphs 1, 2, 3 and 4, respectively). The same relationship for a 3N electrolyte with no excess of H<sub>3</sub>BO<sub>3</sub> at 20, 30, 40 and 50°C is shown in Figure 4 (graphs 1 to 4). A 3N electrolyte was also used for investigating the effect of the pH number which was varied between 1 and 5 by means of HBF<sub>4</sub> or sodium iodide additions. It was found that at pH = 5, the electrolyte is unstable and contains black, insoluble particles (most likely Ni(OH)<sub>2</sub> with

basic salts) held in suspension. Pitting occurs and a dendritic deposit is obtained which at low current densities

(1 to 5  $A/dm^2$ ) becomes dark. At pH = 4, low current

Card3/8

 $(\mathbf{r})$ 

Electrode Processes in Electro-deposition of Nickel From Fluoborate Electrolytes

densities result in a dark deposit, while dendrites are formed at high current densities. At pH = 1 or 2, intensive evolution of hydrogen takes place on the cathode surface, the evolved gas forming bubbles which adhere to the cathode and cause pitting. Best quality deposits are obtained at pH = 3. Yield per unit current varies in all cases between 89.6 and 99.7%, increasing with increasing current density and at high pH (3 to 4) values, and falling sharply at low current densities and at pH = 1 or 2. In the next stage of the investigation the anodic processes were studied. Four types of electrolytes were used containing (in g/litre): (A) 25 Ni(BF<sub>4</sub>)<sub>2</sub>, 68.5 F<sub>1</sub>, 138.7 F<sub>2</sub> and 34.4 B; (B) same as (A) plus 15 NiCl<sub>2</sub>.6H<sub>2</sub>O; (C) 240 NiSO<sub>4</sub>.7H<sub>2</sub>O, 30 H<sub>3</sub>BO<sub>3</sub>; (D) same as (C) plus 20 NaCl. Cathodes were made of electrolytic nickel or of non-passivating nickel containing C 0.2%, Si 0.2% and S 0.005 (Ref 12). To reduce to minimum the difference between their true and the geometric surface areas, the cathodes were

Card4/8

Electrode Processes in Electro-deposition of Nickel From Fluoborate Electrolytes

polished first mechanically and then electrolytically (to remove the plastically deformed layer). The results, in the form of graphs showing the relationship between the anodic current density and the anode potential, are reproduced in Figure 5: graph (1) - non-passivating nickel anode in electrolyte C; graph (2) - as (1) but electrolyte Dused; graph (3) - non-passivating nickel anode in electrolyte A; graph (4) - as (3) but in electrolyte B; graphs (5) and (6) - electrolytic nickel anode in electrolytes C and D, respectively. When the ratio of the anode and cathode surface areas was  $S_a/S_k = 2:1$ , the yield of the dissolved metal per unit current was high even in the absence of chlorides in the electrolyte but for Sa/Sk = 1:1, a slightly lower yield was obtained. the bath was operated for the equivalent of 800 A.hour per 1 litre of electrolyte, the concentration of the nickelbearing salt in the solution was unchanged and only a slight rise in the pH number was observed. In their Card5/8 conclusions the authors state that: i) the main advantage

Electrode Processes in Electro-deposition of Nickel From Fluoborate Electrolyte

to be gained by using the fluoborate electrolyte instead of a sulphate solution for nickel plating is that the process can be intensified, i.e. higher current densities can be employed without affecting the quality of the deposit and yet without reducing the yield per unit current. maximum permissible current density can be increased by increasing the Ni concentration in the electrolyte (up to 3N) and by using higher temperatures; 11) when the concentration of  $H_3\bar{B}O_3$  in the electrolyte is increased, the cathode potential is reduced and so is the maximum permissible current density. In spite of this effect, which is probably due to partial dissociation of Ni(BF4)2 to Ni(BF3OH)2 and to a decrease in the activity of the nickel ions in the electrolyte, it is recommended to maintain the  $H_3BO_3$  concentration slightly (approx. 15 g/litre) above the value corresponding to the stoichiometric ratio, since free H3BO3 improves the stability of the electrolyte and makes it less reactive;

APPROVED FOR RELEASE: 03/13/2001 CIA-RDP86-00513R000928910004-8"

Card6/8

SOV/149-58-5-14/18
Electrode Processes in Electro-deposition of Nickel from Fluoborate
Electrolyte

iii) the effect of chlorides introduced in the electrolyte in the form of NiCl<sub>2</sub>.6H<sub>2</sub>O in amounts up to 15 g/litre is beneficial, since they reduce polarisation. However, at high (more than 30 g/litre) chlorides concentrations, the maximum permissible current density is lower and the quality of the deposit is adversely affected. At 50 °C, the effect of the chlorine ions becomes insignificant, the effect of the chlorine ions becomes insignificant, most likely owing to the reduced adsorption of these ions on the cathode surface and to sufficiently high activity of the anode, particularly when made of non-passivating of the anode, particularly when made of non-passivating material. Owing to the latter factor, the fluoborate electrolytes are quite stable, so that in operation it is only necessary to replenish the fluoboric acid in order to maintain constant pH, since the anodic yield per unit current is slightly higher than the cathodic; (iv) the optimum value of the pH number of a fluoborate solution for nickel plating is between 3 and 3.5. At solution for nickel plating is between 3 and 3.5. At pH = 1, the yield per unit current is too much affected by the variation of the current density, while at

Card7/8

Electrode Processes in Electro-deposition of Nickel from Fluoborate

Electrolyte

pH = 4.5, the electrolyte becomes unstable and subject to hydrolysis and dark deposits are obtained; (v) tendency to pitting is one of the shortcomings of the fluoborate solutions for nickel plating. This undesirable effect can be minimised by application of stirring and by addition of reagents reducing the surface tension of the electrolyte.
There are 5 figures, 1 table and 12 references, 3 of which are Soviet and 9 English.

Moskovskiy institut tsvetnykh metallov i zolota. ASSOCIATION:

Kafedra elektrokhimii i korrozii (Moscow Institute of Non-ferrous Metals and Gold. Chair of Electro-

chemistry and Corrosion.)

January 14, 1958 SUBMITTED:

card 8/8

PHASE I BOOK EXPLOITATION

sov/2693

25(1)

Layner, Vladimir Il'ich, Professor, Doctor

Gal'vanicheskiye pokrytiya legkikh splavov (Electroplating of Light Alloys) Moscow, Metallurgizdat, 1959. 137 p. 6,200 copies printed.

Reviewers: A.V. Shreyder, Candidate of Technical Sciences, and L.I. Stoklitskiy, Engineer; Ed.: A.V. Shreyder; Ed. of Publishing House: M.S. Arkhangel'skaya; Tech. Ed.: L.V. Dobuzhinskaya.

PURPOSE: This book is intended for engineers and technicians in electroplating shops. It may also be useful to students of vuzes.

COVERAGE: The author discusses the electroplating of articles made of aluminum, magnesium, beryllium, and titanium alloys. Preparatory operations and methods of application are described. Chrome-plating processes for increasing wear resistance and for decorative and protective purposes are treated in detail. The decorative and protective purposes are treated in detail. The author thanks Yu.A. Velichko, G.S. Galimova, Z.G. Smorodova, author thanks Yu.A. Velichko, G.S. Galimova, T.M. Marenkova for their G.S. Konstantinova, V.V. Syagina, and T.M. Marenkova for their

Card 1/5

assist	ating (Cont.)  ance. There are 70 references: 7 Soviet, 50 English, 8, and 5 French.	
TABLE OF	CONTENTS:	
Preface		3
I. Ge II. M	lectroplating of Aluminum Alloys neral information ethods of preparing surfaces of aluminum articles for lectroplating Mechanical preparation Chemical preparation Electrochemical oxide coating Zincate method Electrolytic deposition of very thin layers of zinc and brass Double treatment in zincate solution Treatment in fluoride solutions	55 88 918 25 378 43

APPROVED FOR RELEASE: 03/13/2001 CIA-RDP86-00513R000928910004-8"

III.	Protective and decorative charticles	frome practing or aluminum	51
1.	Sequence of operations in p	protective and decorative	_
2.	chrome plating of aluminum Electroplating of aluminum	articles prepared by the	51
	zincate method .	articles propared by the	53
3.	Annealing of aluminum artic		53 58
4.	Nickel plating of aluminum application of thin layers		61
5.	Four-stage process of chrom		
6	Ni-Cu-Ni-Cr) Corrosion testing		66
	Chemical nickel-plating of	aluminum	67 69
	Chrome plating for wear resis	stance	70
1.		or wear resistance	71 78
3.			81
	Inplating	-	87
VI.	Other types of electroplating		91
ard 3/5			
2. 3. <b>v.</b> T:	Chrome-plated aluminum-allowed Fatigue strength of chrome- Inplating Other types of electroplating	y cylinders plated aluminum alloys	1

e e e e e e e e e e e e e e e e e e e			
Electro	plating (Cont.)	<b>sov/</b> 2693	
I.	Electroplating of Magnesium Allo General information	95	
	Preparing surfaces of magnesium Porosity of coatings on magnesi		
IV.	Soldering of copper-plated magnetic strong solutions of parts for the	esium 104	
	earth satellite Comparative corrosion resistance	106	
VI.	and zinc after protective and de		
Ch. 3.	Electroplating of Beryllium	115	
I.	Electroplating of Titanium Allog General information Electrochemical treatment of ti	120 tanium with a mixture of	
III.		tures of acetic and hydro-	
and II	fluoric acids and acetic and ol	hromic acids 131	<b>3.</b>
Card 4/	<b>D</b>		
:			